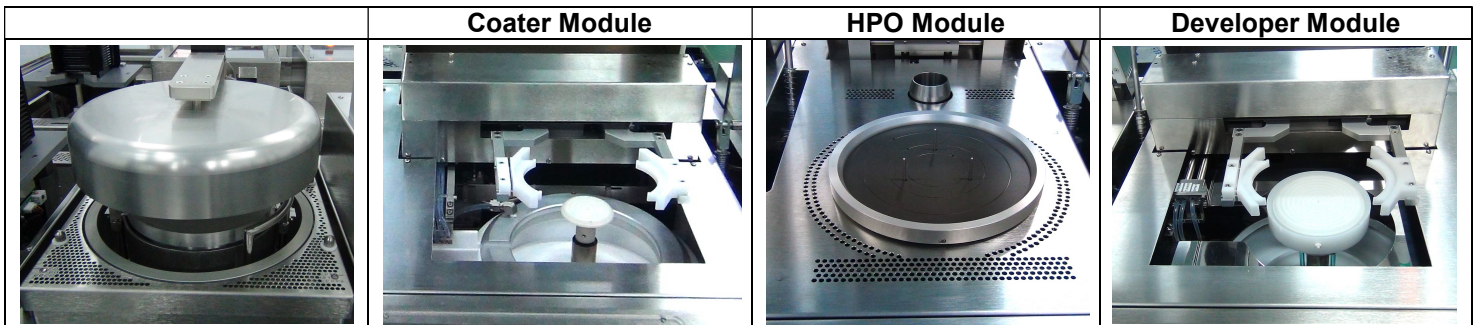


PCT-150RRE STAND ALONE TRACK SYSTEM
FOR R&D WITH TRACK STAND ALONE (1 VPO, 1 COATER, 1 DEVLOPER, 1 HPO) TOOL SET
Please contact Sales sales@picotrack.com for more information



Track System Specification	Description								
System designed	US Standard System								
System Configuration	<table border="1"> <tr> <td>VPO</td> <td>COATER</td> <td>HPO</td> <td>DEV</td> </tr> <tr> <td colspan="4" style="text-align: center;">150RRE STAND ALONE SYSTEM</td> </tr> </table>	VPO	COATER	HPO	DEV	150RRE STAND ALONE SYSTEM			
VPO	COATER	HPO	DEV						
150RRE STAND ALONE SYSTEM									
System dimension	Length: 78.5" ; Width: 28" ; Height: 62"								
Wafer size (workable dual size)	Up to 6" (150mm) or 4" & 6" auto conversion								
Wafer shape	Round/Square/Rectangular/Triangle/Special								
Wafer material	Silicon/Sapphire/GaAs/ Ceramic...								
Wafer handling	Manual load/unloading								
System controller	PC & PLC Controller with Windows OS based								
Chemical canister cabinet	Solvent (EBR, HMDS, Cleaning...), developer liquid								
Pumps cabinet	Photoresist pumps (IDI, Cybor..), dispenser unit, & photoresist bottles								
Coater	1 module								
Catch Cup Set	Fixed position								
Spindle Unit	Up/down motion								
Maximum spin speed	6000 rpm								
Spin motor type	Servo								
Spin speed accuracy	± 3 rpm								
Acceleration range	0-50000 rpm/sec								
Dispense arm accuracy	± 0.1 mm								
Wafer centering	± 0.1 mm								
Dispense arm motion control	Stepper motor & driver PCB								
Dispense arm & nozzles	3x or more (3/16" or 1/4" OD) (Standard)								
Dispense method	Static and traverse								
Pre-dispense function	Yes								
Top/Bottom EBR	Yes								
Catch-cup rinse(CCR)	Optional								
Cleaning tip nozzle	Optional								
Humidity & Temperature control	Optional								
Photoresist temperature control	Optional (≤ 1°C; 10-50°C range)								
Developer	1 module								
Catch Cup Set	Fixed position								
Spindle Unit	Up/down motion								
Maximum spin speed	6000 rpm								
Spin motor type	Servo								
Spin speed accuracy	± 3 rpm								
Acceleration range	0-50000 rpm/sec								
Spin direction	Clockwise (+) & counter clockwise (-)								
Dispense arm motion control	Stepper motor drive and rotation								
Dispense arm accuracy	± 0.1 mm								
Wafer centering tolerance	± 0.1 mm								
Dispense arm nozzles	1 Spray+ 1 Stream or 2 spray+ 2 stream (Standard)								
Negative developer nozzles	Cone or fan spray with N2 air assist (Upon request)								
Developer dispense type	Stream, Puddle, Fan spray, Cone spray....								
Dispense method	Static, traverse and sweep								

DI water top and back side rinse	Yes
N2 Air Ring back side	Yes
N2 Blow-off top nozzle	Optional
Developer liquid Temp. controller	Optional ($\leq 1^{\circ}\text{C}$; 10-50 $^{\circ}\text{C}$ range)
Vapor Prime Ovent (VPO)	1 module
VPO block type	Aluminum anodized with vacuum slots
VPO Temperature controller	Watlow P.I.D with over heating protection
Temperature thermal probe	RTD or TC
Temperature range	Up to 200 $^{\circ}\text{C}$, Δt : 50 $^{\circ}\text{C} \leq 200\text{s}$
Temperature uniformity	$\pm 1^{\circ}\text{C}$ (25-150 $^{\circ}\text{C}$), $\pm 2^{\circ}\text{C}$ (151-200 $^{\circ}\text{C}$)
HMDS prime method	Fume shower on top by N2 pressurized with bubbler
Wafer contact angle	$\geq 65^{\circ}$ on prime silicon wafer
Contact angle uniformity	$\leq 1.5^{\circ}$ on prime base silicon wafer
Wafer carrier	3 pins controlled by stepper motor
Bake method	Contact, vacuum & purge bake
Hot Plate Oven (HPO)	1 module
HPO block type	Aluminum anodized with vacuum slots or standoff proximity
Temperature thermal probe	RTD or TC
HPO Temperature controller	Watlow P.I.D with over heating protection
Temperature range	25-250 $^{\circ}\text{C}$, Δt : 50 $^{\circ}\text{C} \leq 200\text{s}$ (>250 $^{\circ}\text{C}$ option)
Temperature uniformity	$\pm 1^{\circ}\text{C}$ (25-150 $^{\circ}\text{C}$), $\pm 2^{\circ}\text{C}$ (151-250 $^{\circ}\text{C}$)
Wafer carrier	3 pins controlled by stepper motor
Bake method	Contact/ Proximity bake/ or fixed proximity